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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION: GEUN-YOUNG YEOM, ET. AL.

FOR: METHOD OF ETCHING SEMICONDUCTOR DEVICE USING NEUTRAL
BEAM AND APPARATUS FOR ETCHING THE SAME

AMENDMENT

The Assistant Commissioner of
Patents and Trademarks
Washington, DC 20231

Dear Sir:

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Date of Deposit November 8, 2001
I hereby certify that this paper or fee is being deposited
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D.C. 20231.
Jennifer Watson
(Typed or printed name of person mailing paper or fee)
[Signature]
(Signature of person mailing paper or fee)

Before examining the present application, please preliminarily amend the
specification, claims and abstract as follows:

IN THE CLAIMS

Please replace claims 1-13 with the following rewritten versions:

- A1
- Sub B-7
1. [(Amended)] A method of etching a semiconductor device using a
neutral beam comprising:
extracting an ion beam having a predetermined polarity from an ion source to
accelerate the ion beam;
reflecting an accelerated ion beam by a reflector to neutralize the reflected ion
beam; and
positioning a substrate to be etched in a path of a neutral beam to etch a material
layer on the substrate with the neutral beam.